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Certified to ISO-9001 and 17025

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ION SPUTTER STANDARDS

Geller MicroÅnalytical Laboratory offers ion sputter standards that are manufactured specifically for calibrating sputter ion guns. Thin films of SiO_2, Si_3N_4, and Ta_2O_5 are available. The uniformity is ~ 5%.

Silicon Dioxide
Silicon wafers with thin films of silicon dioxide are currently available with nominal thicknesses of approximately 18.7, 50, 97, and 479 nm.These oxide films are grown with a wet oxygen process which insures a higher degree of uniformity than available using other processes. The wafers are 4" in diameter and cost $475.00 each.

Silicon Nitride
100nm stoichiometric Silicon Nitride (CVD) films deposited on a ~1 X 3 cm piece of silicon wafer are $300.00.

Tantalum Pentoxide
Films of tantalum pentoxide are anodically grown on 0.5mm thick tantalum foil. The standards are ~ 37 X 37mm and cost $300.00. Thicknesses of 55.5 nm and 126.6 nm are currently available. The standards are measured (using electron beam excited x-ray analysis) against the NPL (NIST counterpart in the U.K.) S7B83"B" and "D" standards which are 100 and 30nm, respectively. The thickness accuracy is ÷5%,

Nickel/Chromium
12 alternating layers of approximately 50nm each over silicon. See data sheet.

Please check for new additions. All items subject to availability.